







The latest 20 years are displayed View a graph with all years.



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		2013	2014	2015	2016	2017	Total	Average Citations per Year
	the checkboxes to remove individual items from this Citation Report estrict to items published between 1900 v and 2017 v Go	228	298	278	297	8	3180	106.00
1.	Continuous analytic I-V model for surrounding-gate MOSFETs  By: Jimenez, D; Iniguez, B; Sune, J; et al.  IEEE ELECTRON DEVICE LETTERS Volume: 25 Issue: 8 Pages: 571-573  Published: AUG 2004	16	16	9	8	0	189	13.50
2.	ON THE BREAKDOWN STATISTICS OF VERY THIN SIO2-FILMS  By: SUNE, J; PLACENCIA, I; BARNIOL, N; et al.  THIN SOLID FILMS Volume: 185 Issue: 2 Pages: 347-362 Published: MAR 1990	3	10	3	2	0	177	6.32
3.	New physics-based analytic approach to the thin-oxide breakdown statistics  By: Sune, J  IEEE ELECTRON DEVICE LETTERS Volume: 22 Issue: 6 Pages: 296-298 Published: JUN 2001	15	13	5	12	1	161	9.47
4.	Soft breakdown conduction in ultrathin (3-5 nm) gate dielectrics  By: Miranda, E; Sune, J; Rodriguez, R; et al.  IEEE TRANSACTIONS ON ELECTRON DEVICES Volume: 47 Issue: 1  Pages: 82-89 Published: JAN 2000	1	3	0	2	0	81	4.50
5.	EXPLORATORY OBSERVATIONS OF POSTBREAKDOWN CONDUCTION IN POLYCRYSTALLINE-SILICON AND METAL- GATED THIN-OXIDE METAL-OXIDE-SEMICONDUCTOR CAPACITORS  By: NAFRIA, M; SUNE, J; AYMERICH, X JOURNAL OF APPLIED PHYSICS Volume: 73 Issue: 1 Pages: 205-215 Published: JAN 1 1993	2	1	0	0	0	80	3.20

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6.	Modeling of nanoscale gate-all-around MOSFETs  By: Jimenez, D; Saenz, JJ; Iniguez, B; et al.  IEEE ELECTRON DEVICE LETTERS Volume: 25 Issue: 5 Pages: 314-316 Published: MAY 2004	5	8	4	7	0	78	5.57	
7.	Experimental evidence of T-BD power-law for voltage dependence of oxide breakdown in ultrathin gate oxides  By: Wu, EY; Vayshenker, A; Nowak, E; et al.  IEEE TRANSACTIONS ON ELECTRON DEVICES Volume: 49 Issue: 12  Pages: 2244-2253 Published: DEC 2002	4	1	3	5	0	78	4.88	
8.	Voltage and Power-Controlled Regimes in the Progressive Unipolar RESET Transition of HfO2-Based RRAM  By: Long, Shibing; Perniola, Luca; Cagli, Carlo; et al.  SCIENTIFIC REPORTS Volume: 3 Article Number: 2929 Published: OCT 14 2013	2	24	20	23	1	70	14.00	
9.	Quantum-size effects in hafnium-oxide resistive switching  By: Long, Shibing; Lian, Xiaojuan; Cagli, Carlo; et al.  APPLIED PHYSICS LETTERS Volume: 102 Issue: 18 Article Number: 183505 Published: MAY 6 2013	8	25	17	20	0	70	14.00	
<u> </u>	Power-law voltage acceleration: A key element for ultra-thin gate oxide reliability  By: Wu, EY; Sune, J  MICROELECTRONICS RELIABILITY Volume: 45 Issue: 12 Pages: 1809-1834 Published: DEC 2005	12	3	2	5	0	70	5.38	
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